

# Invited Talk

## Optical Solutions for System-Level Interconnect



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Ecole Centrale de Lyon  
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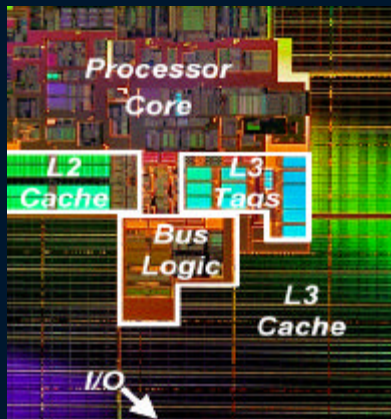
# Outline

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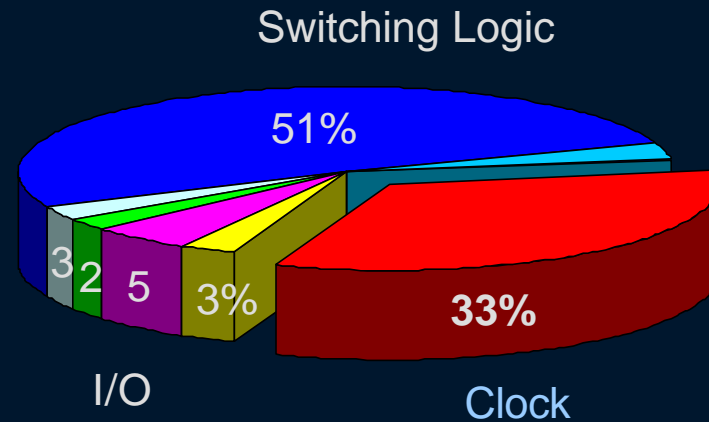
- Context and motivations for optical interconnect
  - ITRS
  - Optical interconnect technology
  - Target applications
- Clock distribution
  - Structure and global design methodology
  - Interface circuit characteristics
  - Calculating losses in passive devices
  - Electrical-optical comparison
- Wavelength-reconfigurable networks on chip
  - Target functionality
  - Modelling and design environment
  - Architecture of reconfigurable network

# Context

- the interconnect problem: "For the long term, material innovation with traditional scaling will no longer satisfy performance requirements. Interconnect innovation with optical, RF, or vertical integration ... will deliver the solution" (International Technology Roadmap for Semiconductors 2003)



Itanium IA-64



# The optical alternative

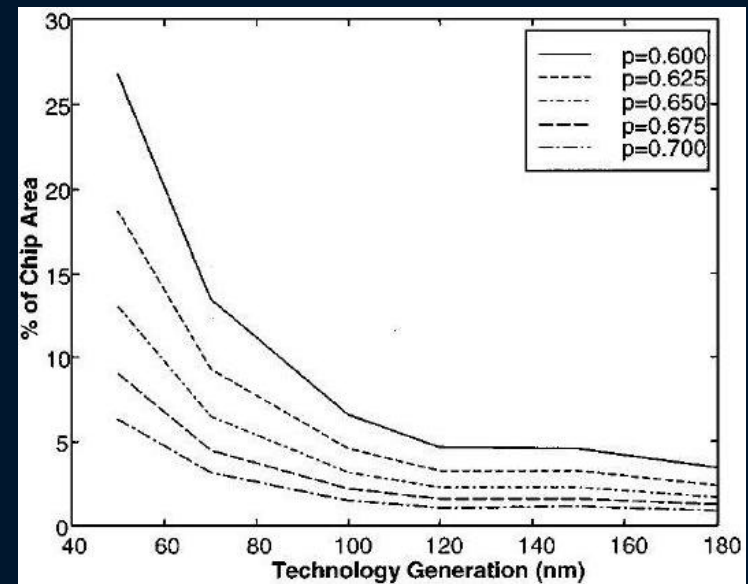
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- optical interconnect to:
  - increase throughput
  - reduce power dissipation
  - alleviate thermal constraints
  - reduce crosstalk
  - decrease skew
  - reduce signal distortion
  - simplify place-and-route for complex circuits
- but:
  - requires high-speed low-power interface circuits
  - process modifications
  - few quantitative analyses exist

# Target applications

## ■ point-to-point (1-1) links?

- routing complexity
- number of repeaters
  - power
  - silicon real estate



## ■ broadcast (1-N) links (clock distribution)

- timing
- clock noise
- power and thermal issues

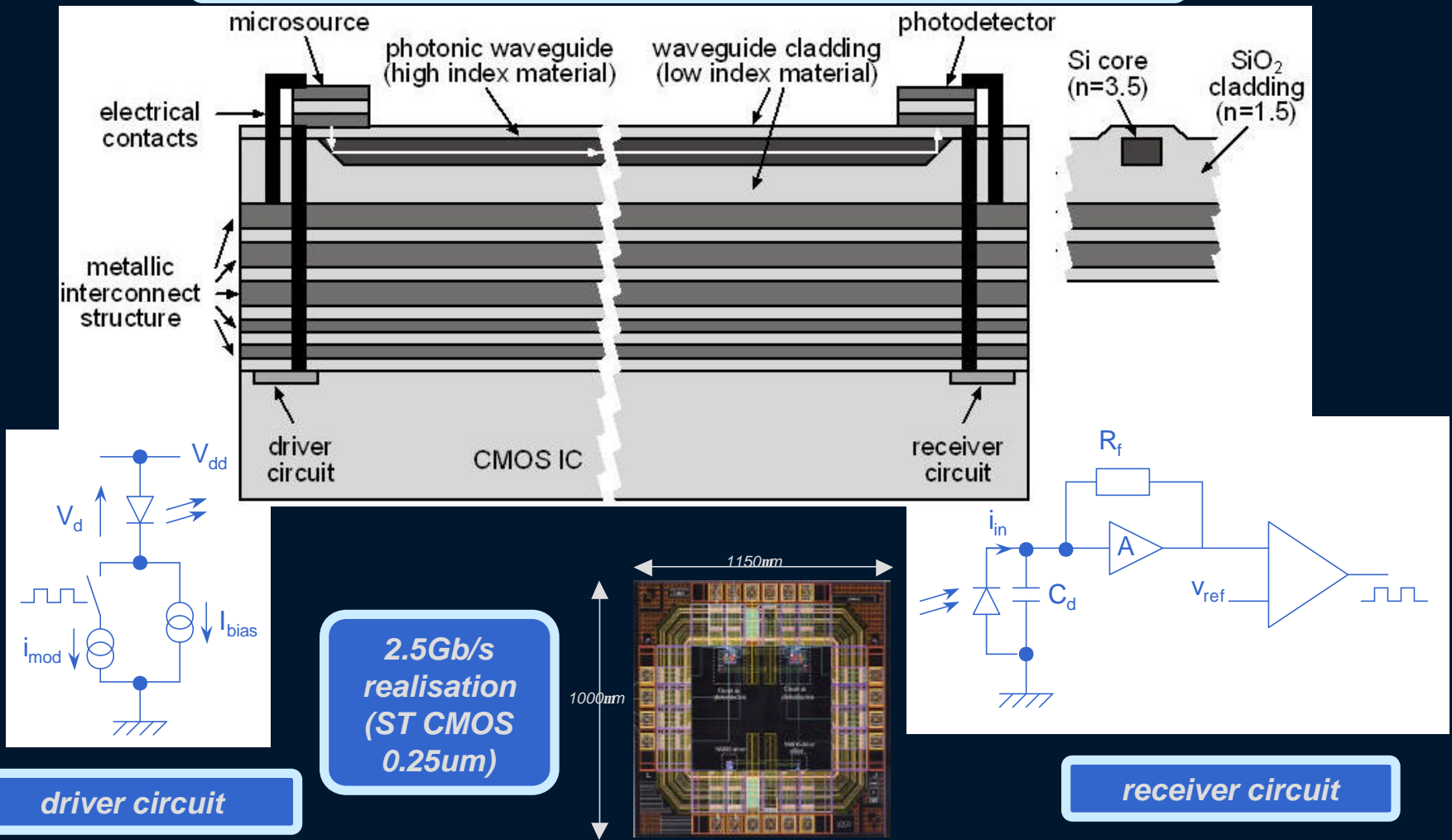
## ■ network (N-N) links

- throughput

*K. Banerjee et al., Proc. IEEE, May 2001*

# Structure of integrated optical interconnect

## heterogeneous III-V on Si integration

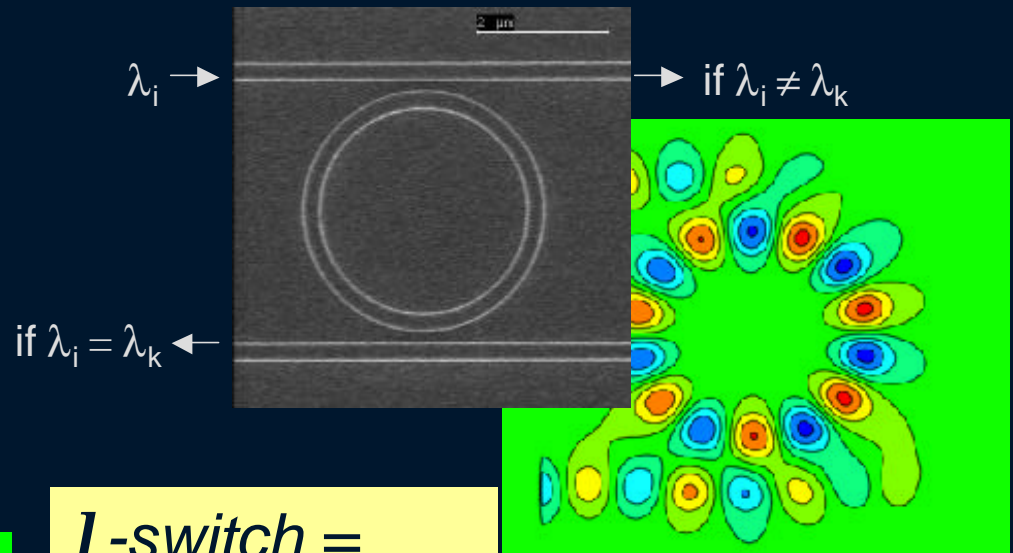
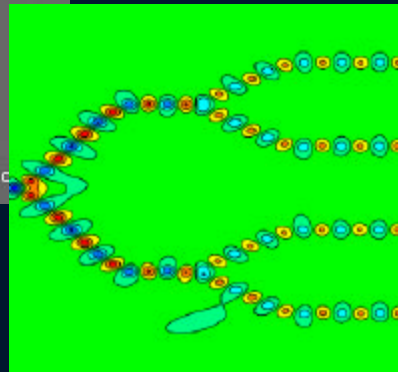
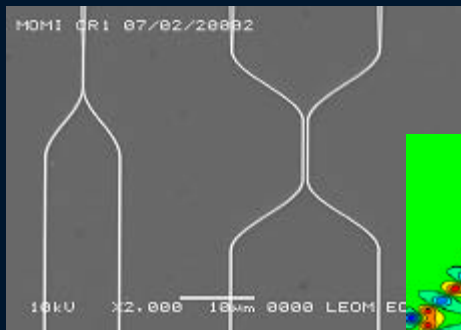


# Passive photonic devices

## couplers, filters, routers

- SOI guides
- Transmission at  $1,55\mu\text{m}$
- intra-chip optical links

*signal transport =  
waveguides and couplers*

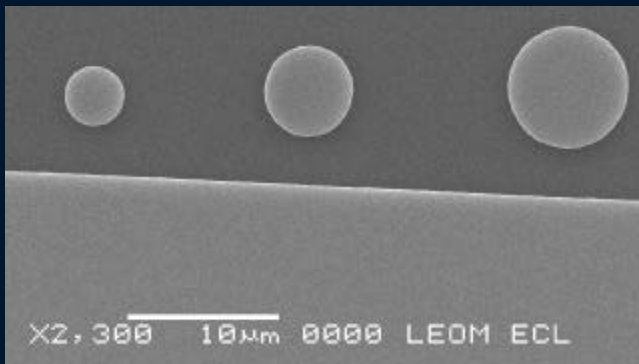
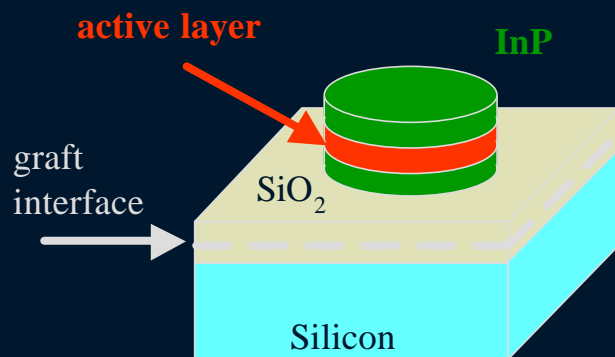


*I-switch =  
add-drop filter*

- resonance mode  $\lambda_k$  depends on disc radius ( $\mu\text{m}$ )

# Active devices

## lasers



C. Seassal et al., IEE Electron. Lett., 2001

## VCSEL

(vertical cavity surface emitting laser) :

- high-wavelength & low-threshold difficult
- coupling difficult (vertical emission)

850nm, 70uA threshold current, 2.6um diameter CMOS compatible VCSEL

(Liu, J.J. et al., Ultralow-threshold sapphire substrate-bonded top-emitting 850-nm VCSEL array, *IEEE Phot. Lett.*, 14, 1234, 2002)

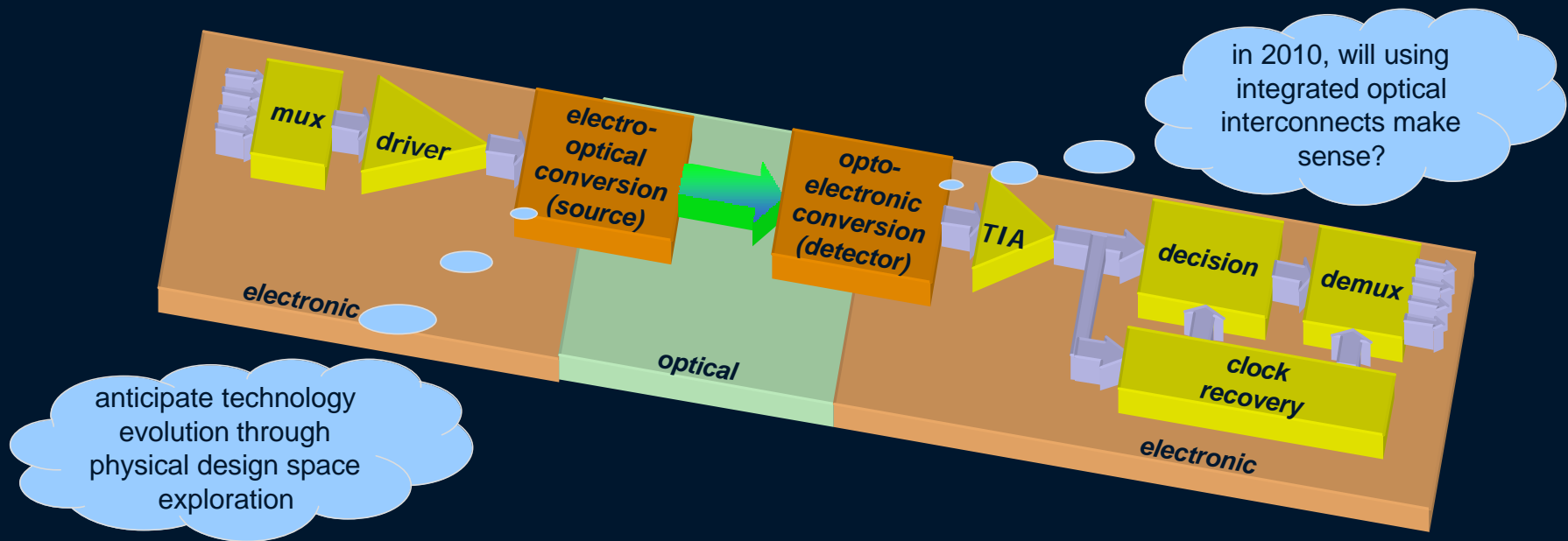
## Microlasers :

- heterogeneous integration (InP on Si)
- Technological simplification
- Coupling to passive SOI guide
  - Thermal dissipation → low threshold

Photonic crystals ...



# Optical interconnect design problems



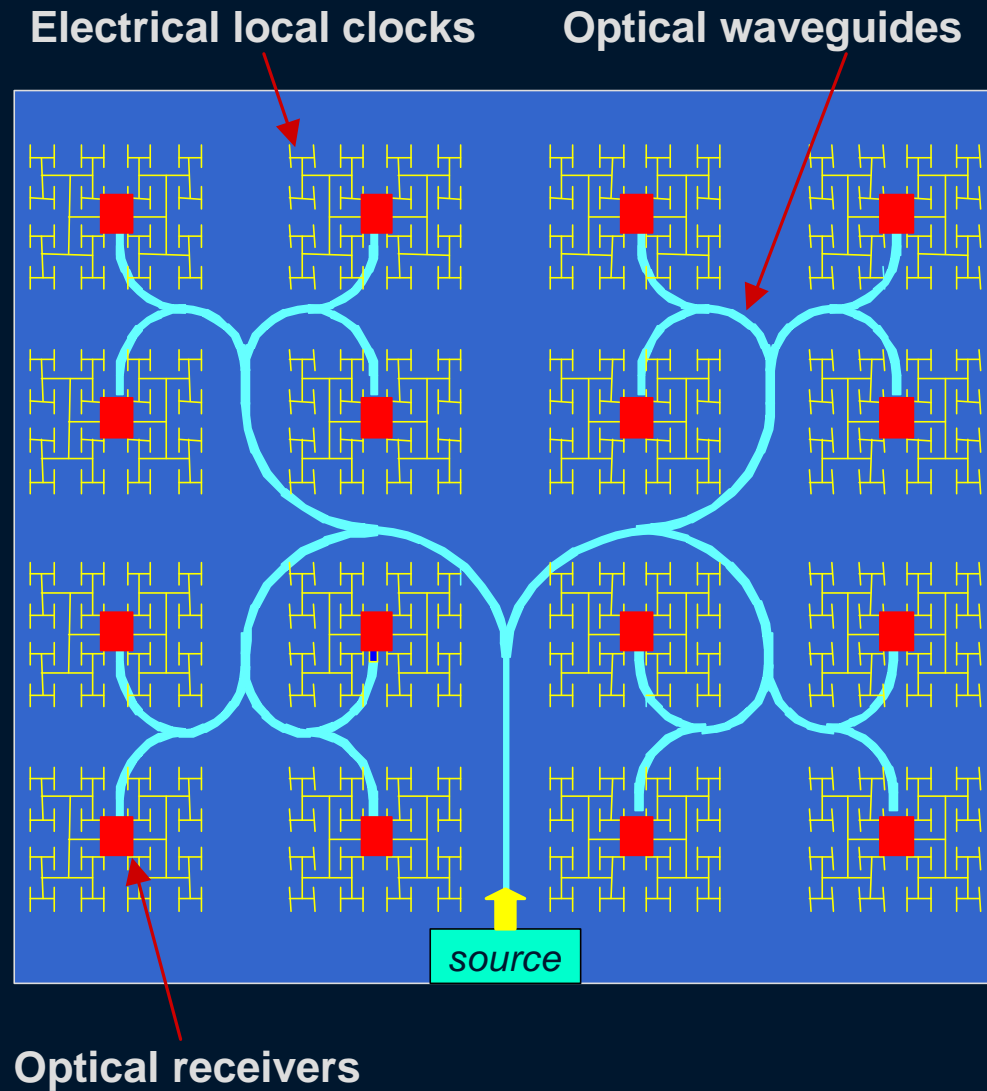
- concurrent design of electronic and optical parts for optical interconnect
  - use of predictive models (technology does not yet exist)
  - generic design methodologies and models

# Outline

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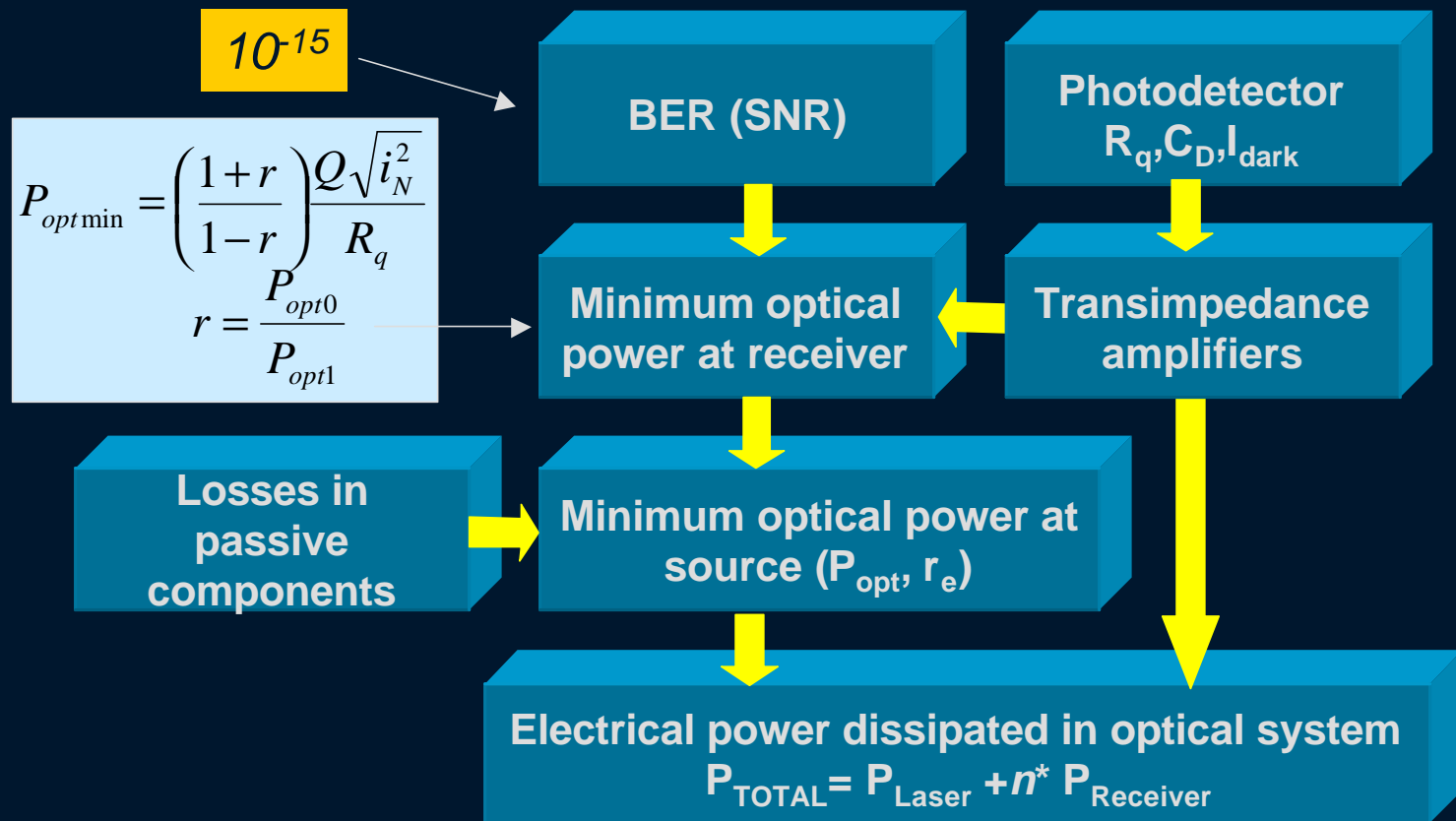
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# Clock distribution network (1-N)



# Calculating the power budget

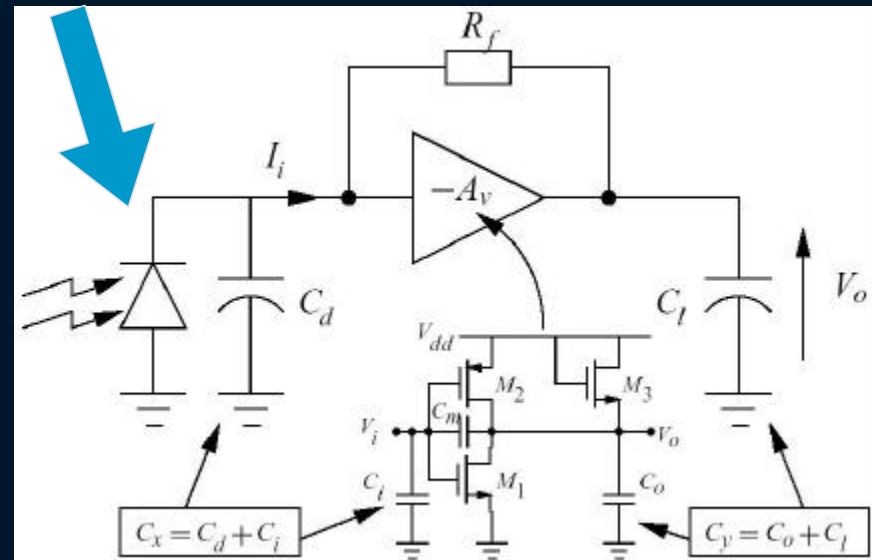
- the route to calculating overall optical interconnect power is based on required signal quality (BER)



# Determining TIA characteristics

- simple analytical equations for transistor characteristics insufficient (>100% error)
- but extraction requires transistor-level schematics
- synthesis

$R_q$  critical for power  
 $C_d$  critical for data rate

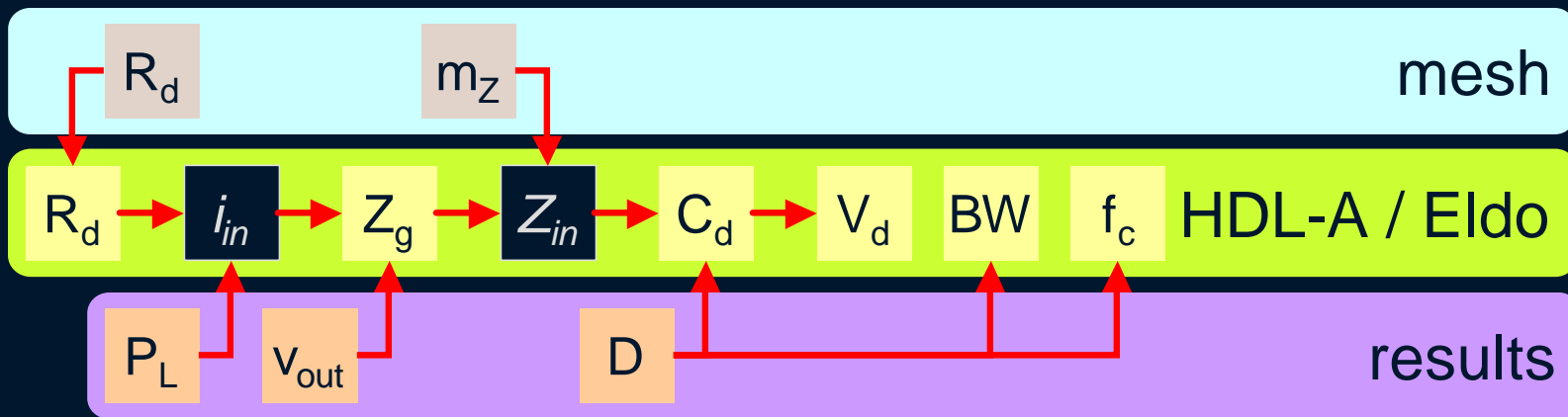
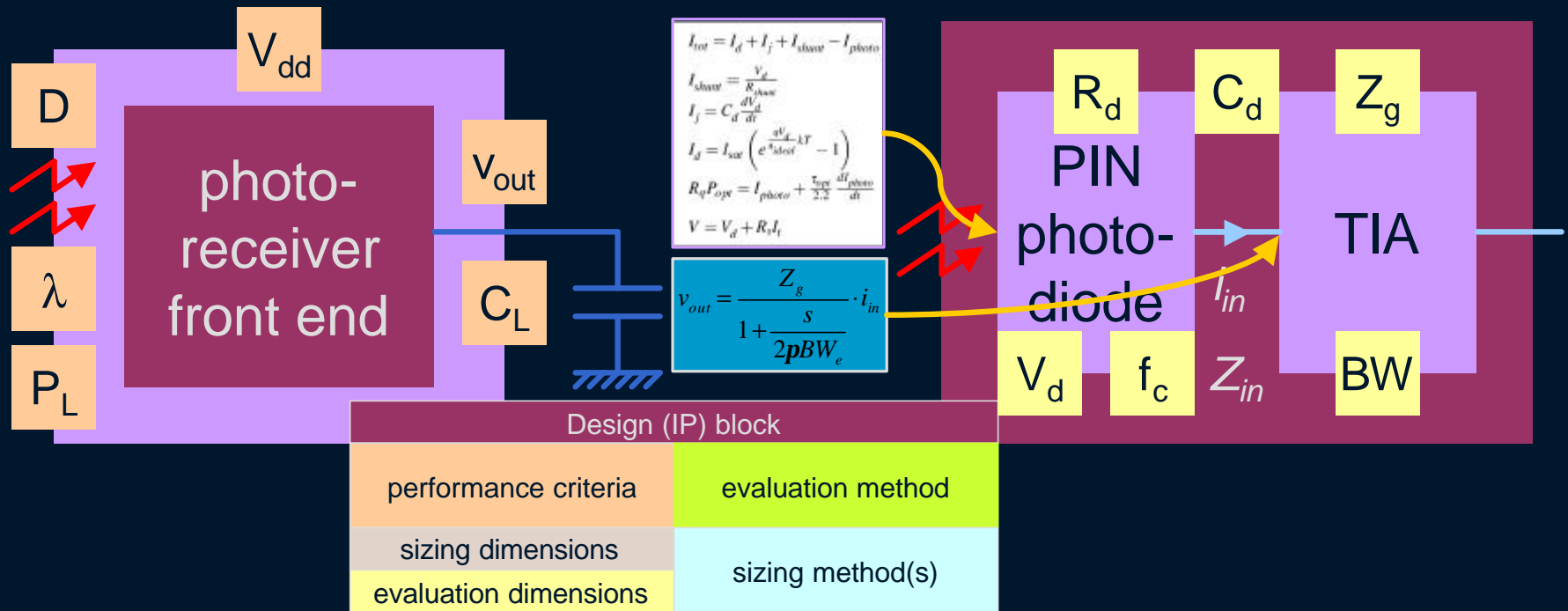


*total noise at photoreceiver*

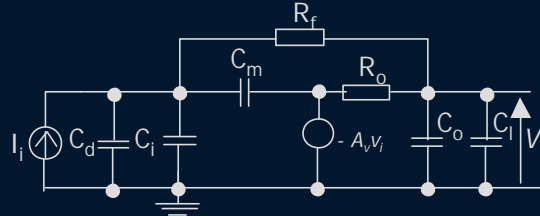
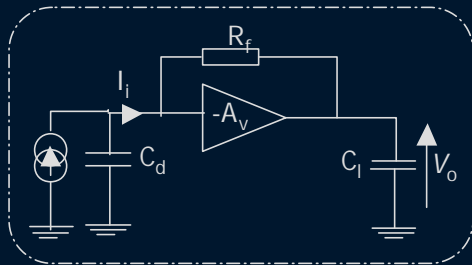
$$\sqrt{i_N^2} = \left( 2q(I_{gate} + I_{dark}) + \frac{4kT}{R_f} \right) \frac{C}{4D} + 4kT\Gamma \frac{C^2}{16p^2 DE} \frac{(2pC_T)^2}{g_m}$$

J.J. Morikuni et al., IEEE J. Lightwave Tech., July 1994

# Photoreceiver front-end IP block



# TIA synthesis



$$Z_{g0} = \frac{R_o - R_f A_v}{1 + A_v}$$

$$\omega_0 = \frac{1}{R_o C_y} \sqrt{\frac{1 + A_v}{M_f (M_x + M_m + M_x M_m)}}$$

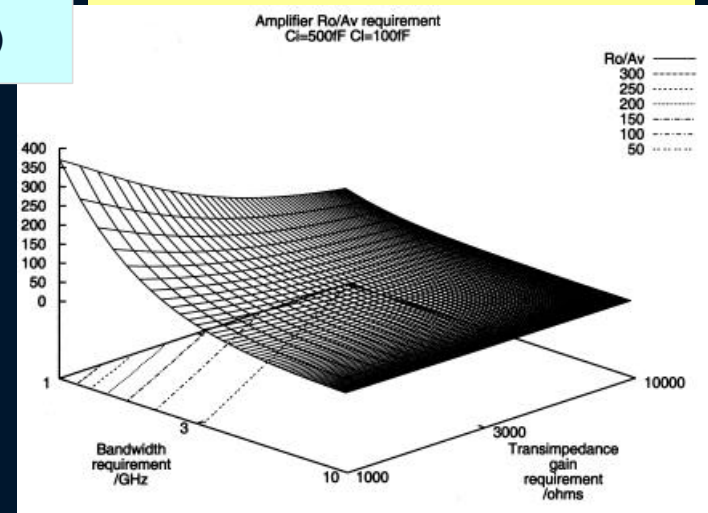
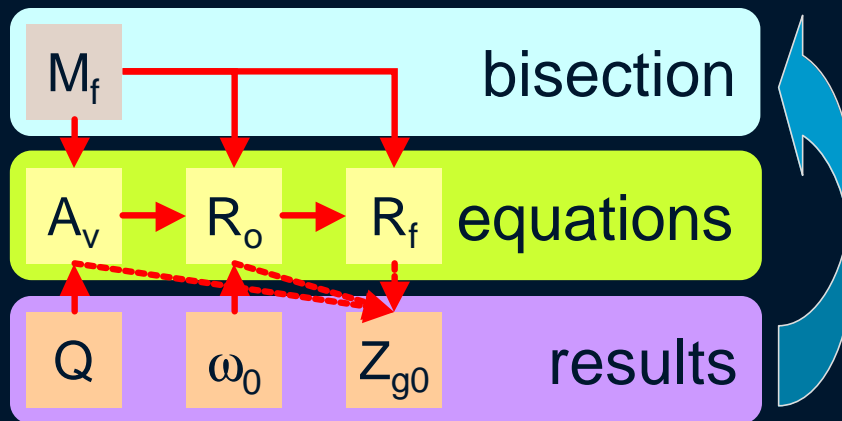
$$Q = \frac{\sqrt{M_f (1 + A_v) (M_x + M_m (1 + M_x))}}{1 + M_x (1 + M_f) + M_m M_f (1 + A_v)}$$

- sizing TIA with iterative procedure
- accurate specification tolerance
- systematic convergence

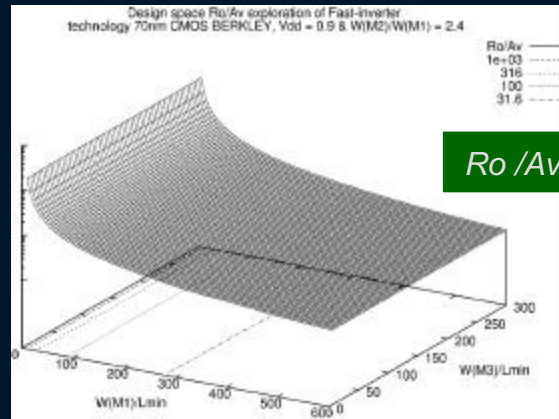
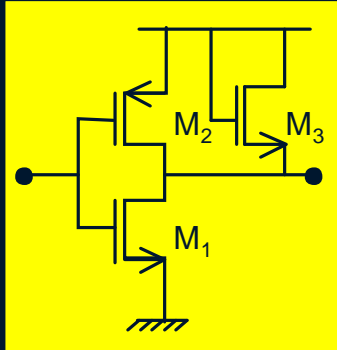
$Q=1/\sqrt{2}$  → Maximize bandwidth

Design (IP) block	
performance criteria	evaluation method
sizing dimensions	sizing method(s)
evaluation dimensions	

"Design ease"  $R_o/A_v$  against bandwidth and transimpedance gain



# Fast inverter IP block



$A_{v0}$	> 7	7.32
$R_o$	< 1k $\Omega$	221 $\Omega$
Pwr	< 4.5mW	4.3mW
$F_i$	= 1	1.005
$V_o$	= 0.5V	0.472

100nm CMOS

Design (IP) block	
performance criteria	evaluation method
sizing dimensions	sizing method(s)
evaluation dimensions	

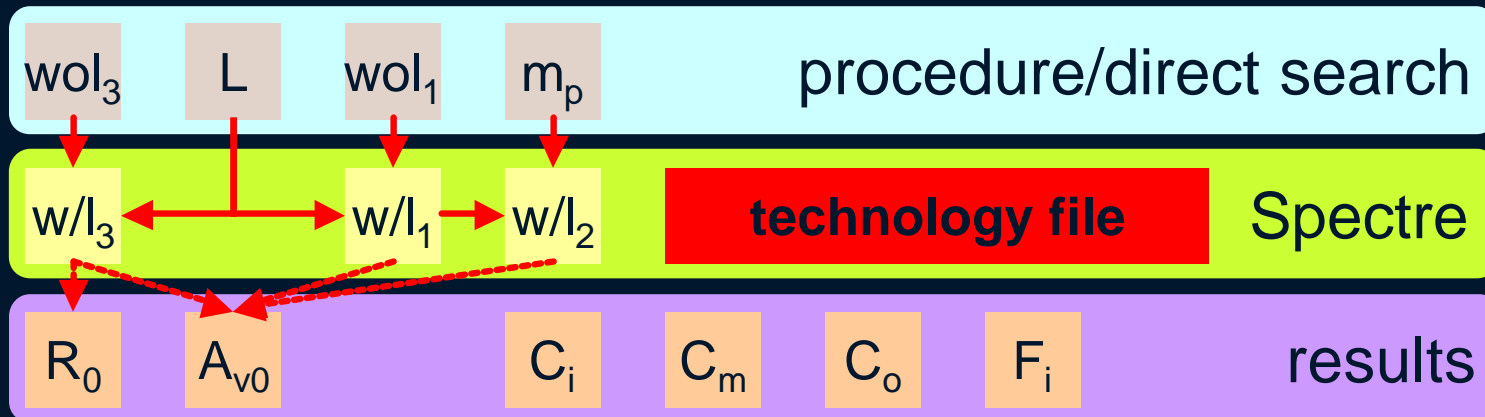
## relations

$$g_{mt} = g_{m1} + g_{m2} = A_v / R_o$$

$$g_{m1} / g_{m2} \approx v_{gst2} / v_{gst1}$$

$$g_{m3} + g_{mb3} + g_{d3} = 1 / R_o - (g_{d1} + g_{d2})$$

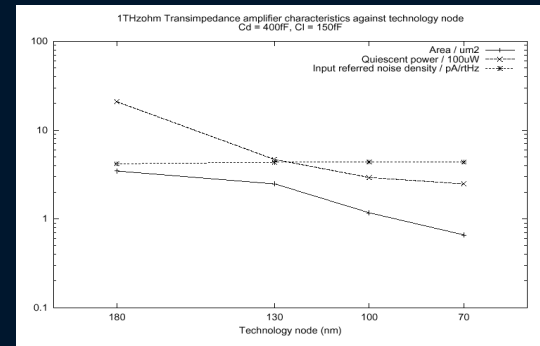
$$F_i = l_1 / (l_2 + l_3)$$





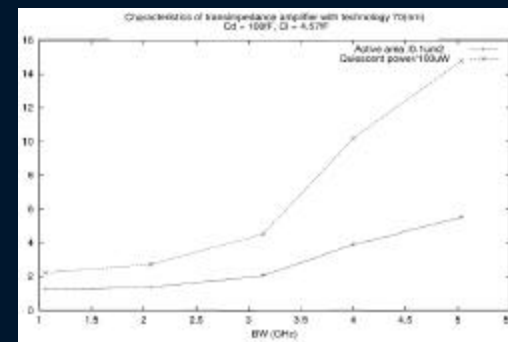
# Predictive design space exploration

- sizing for process nodes 180-130-100-70nm : quantitative predictions for technological evolution
- use of BSIM3v3 transistor model parameters from UC Berkeley (Cao *et al.*, CICC 2000)
- more details at DATE (session 3D Tuesday 16:45)



power / 10  
noise constant  
area / 5

*1THzW TIA design with identical specifications for different technology nodes: validate traditional “shrink” predictions*

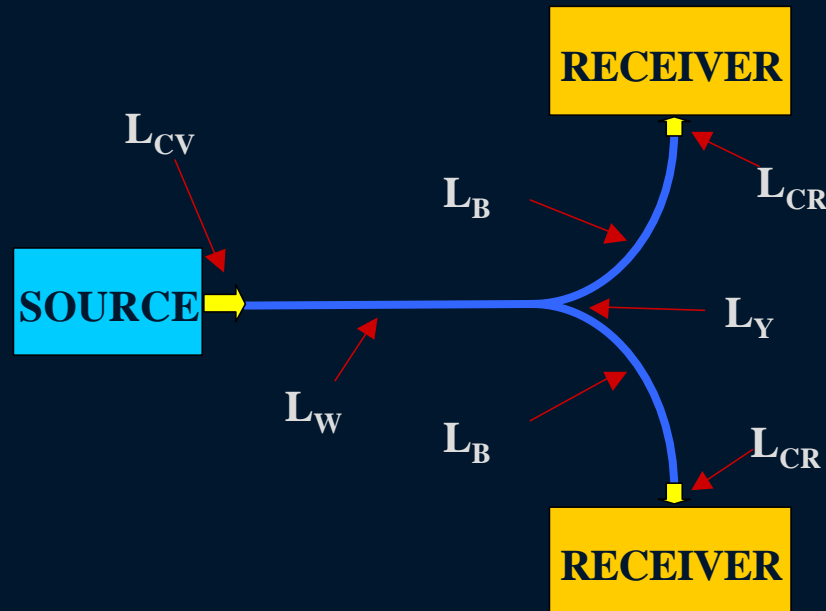


*TIA design @ 70nm node for various BW requirements (all other specifications remain identical)*



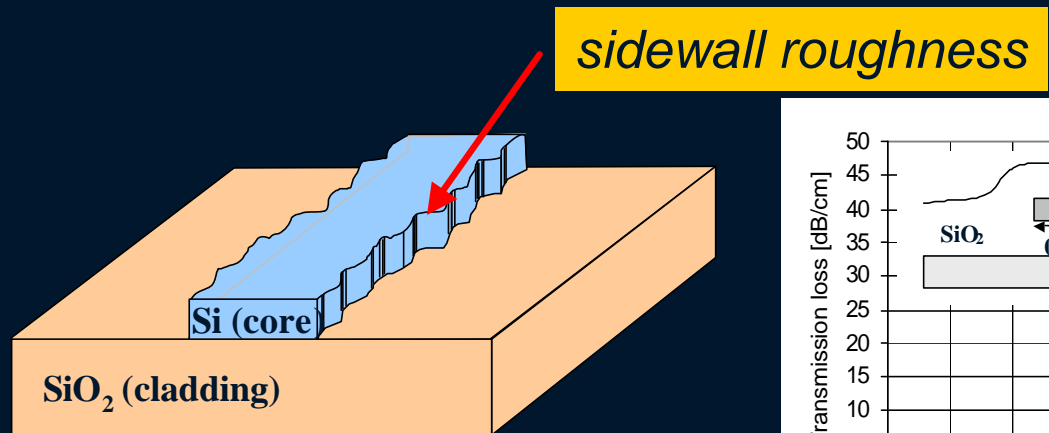
# Losses in an optical link

- $L_{TOTAL} \text{ (dB)} = L_{CV} + L_W + L_Y + L_B + L_{CR}$ 
  - $L_{CV}$  Source-waveguide coupling coefficient
  - $L_W$  Transmission Loss
  - $L_Y$  Y-coupler Loss
  - $L_B$  Bending Loss
  - $L_{CR}$  Waveguide-detector coupling coefficient

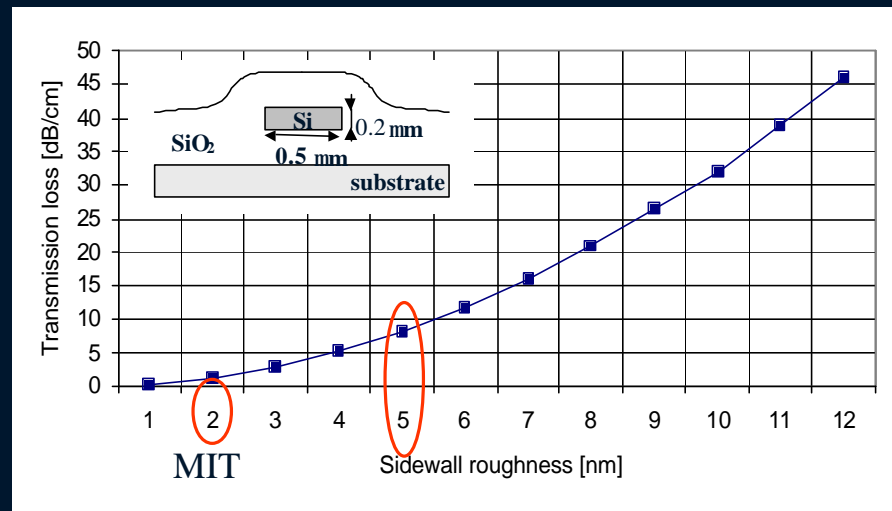


# Transmission loss

- $L_{\text{TOTAL}} \text{ (dB)} = L_{\text{CV}} + L_{\text{W}} + L_{\text{Y}} + L_{\text{B}} + L_{\text{CR}}$



$$L_{\text{W}} = \frac{\sigma^2}{\sqrt{2} k_0 d^4 n_1} g(V) f_e(x, \gamma)$$



$$\sigma = 2 \text{ nm} \Rightarrow 1.3 \text{ dB/cm}$$

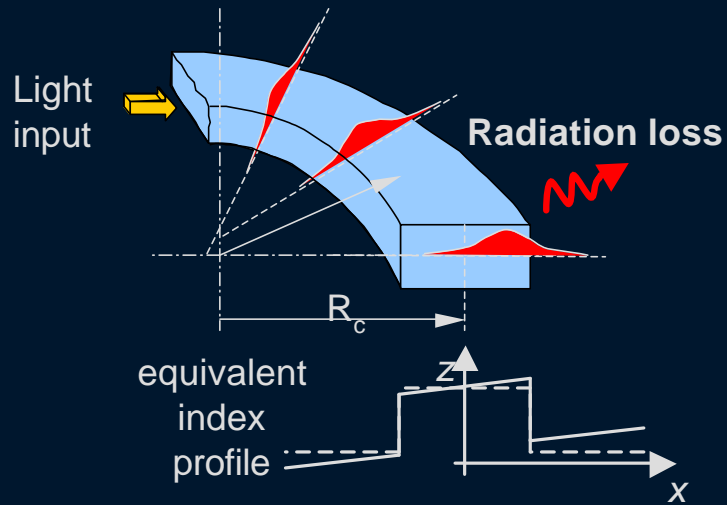
*K. K. Lee et al., Optics Letters, 2001*

# Bending loss

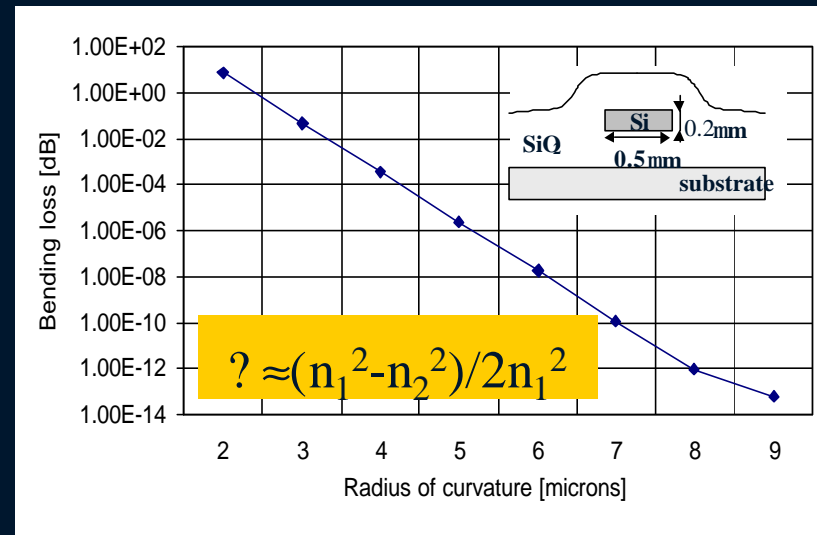
- $L_{TOTAL} \text{ (dB)} = L_{CV} + L_W + L_Y + L_B + L_{CR}$

Modal propagation in a bend

**bends**



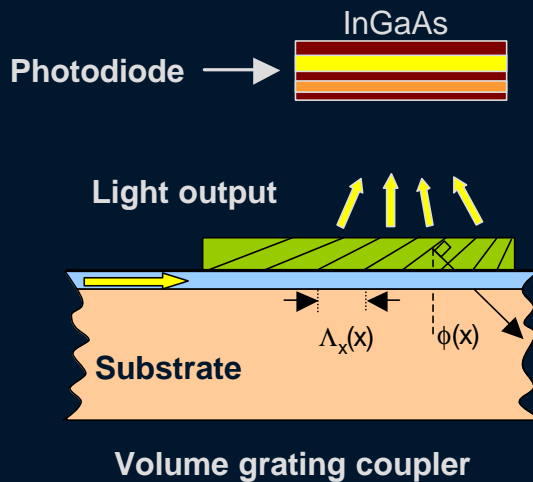
For  $R > 2\mu\text{m}$ ,  $L_B = 0$



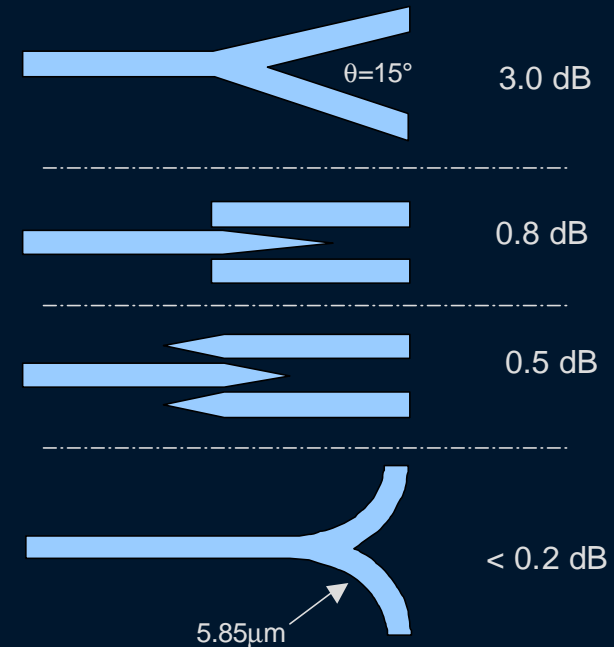
# Other losses

- $L_{TOTAL} \text{ (dB)} = L_{CV} + L_W + L_Y + L_B + L_{CR}$
- $L_{CV}$             Input coupling coefficient (50%=3dB)
- $L_Y$              Y-splitter loss (0.2dB)
- $L_{CR}$             Output coupling coefficient (87%=0.6dB)

Output loss:

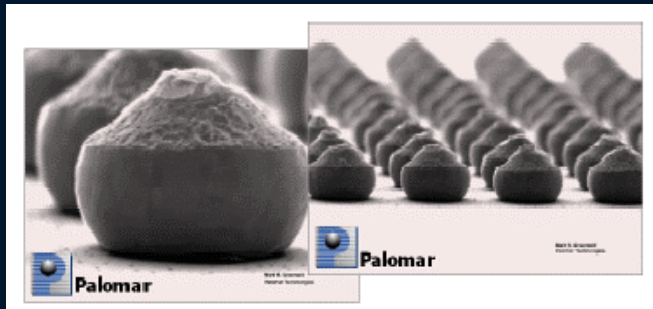


Y-splitter loss

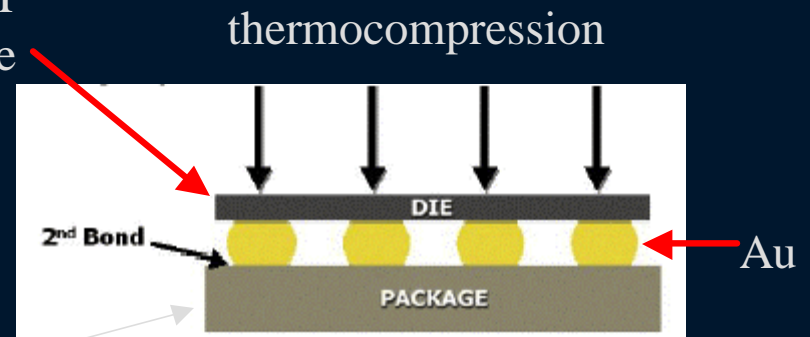


# Bonding issues

- flip-chip is today the most effective and proven technique
  - alignment down to 1um accuracy
  - solder bumps under 10um diameter



InGaAs/InP  
photodiode



CMOS IC

- in the future:
  - molecular bonding
  - direct wafer bonding
  - ...

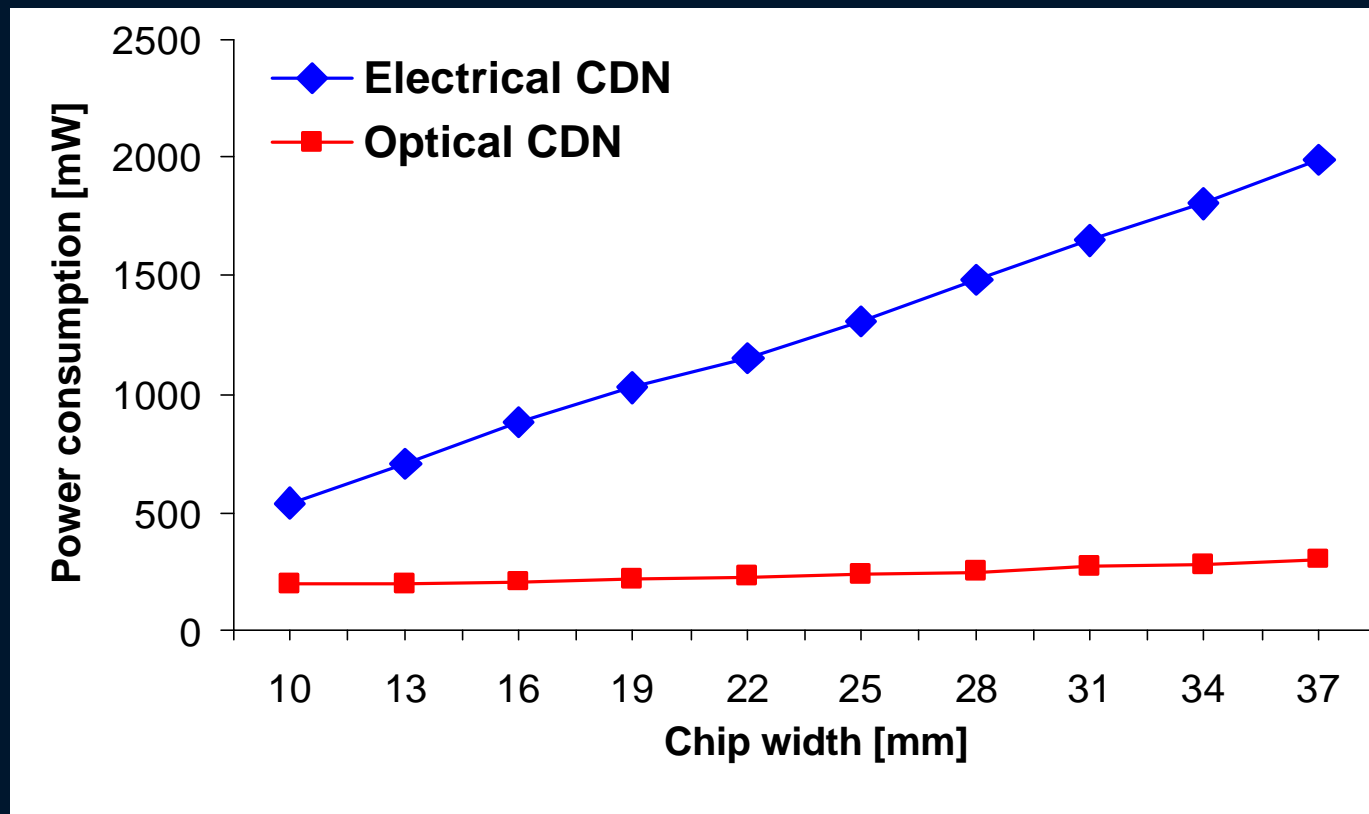
# Investigation conditions and program

Electrical CDN		Optical CDN	
Technology parameters		ITRS roadmap	
Transistors		BSIM3v3 and BSIM4 model parameters [Berkeley Univ.]	
Metallic wires	ITRS roadmap	Optical devices	Existing technology
		InGaAs Photodiode	G8376-02 Hamamatsu Corp.
		(InGaAl)As/InP VCSEL	Amann TU Munchen

- comparison of optical and electrical clock distribution networks:
  - power vs. chip size
  - power vs. operating frequency
  - power vs. number of distribution points
  - power vs. technology node
  - power vs. sidewall roughness

# Electrical-optical comparison

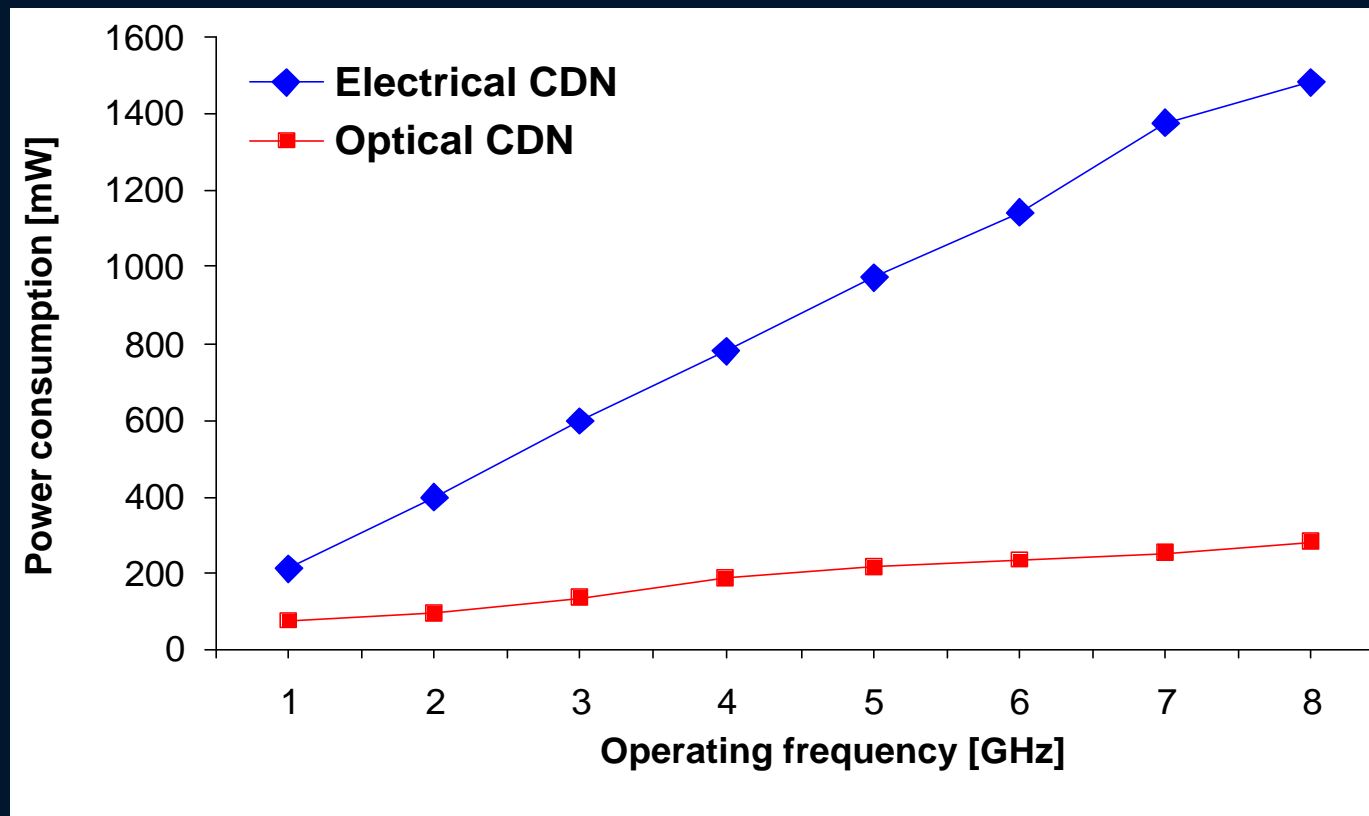
- comparing optical clock distribution power dissipation for varying chip size
- @70nm node, 5.6GHz, 256 drop points





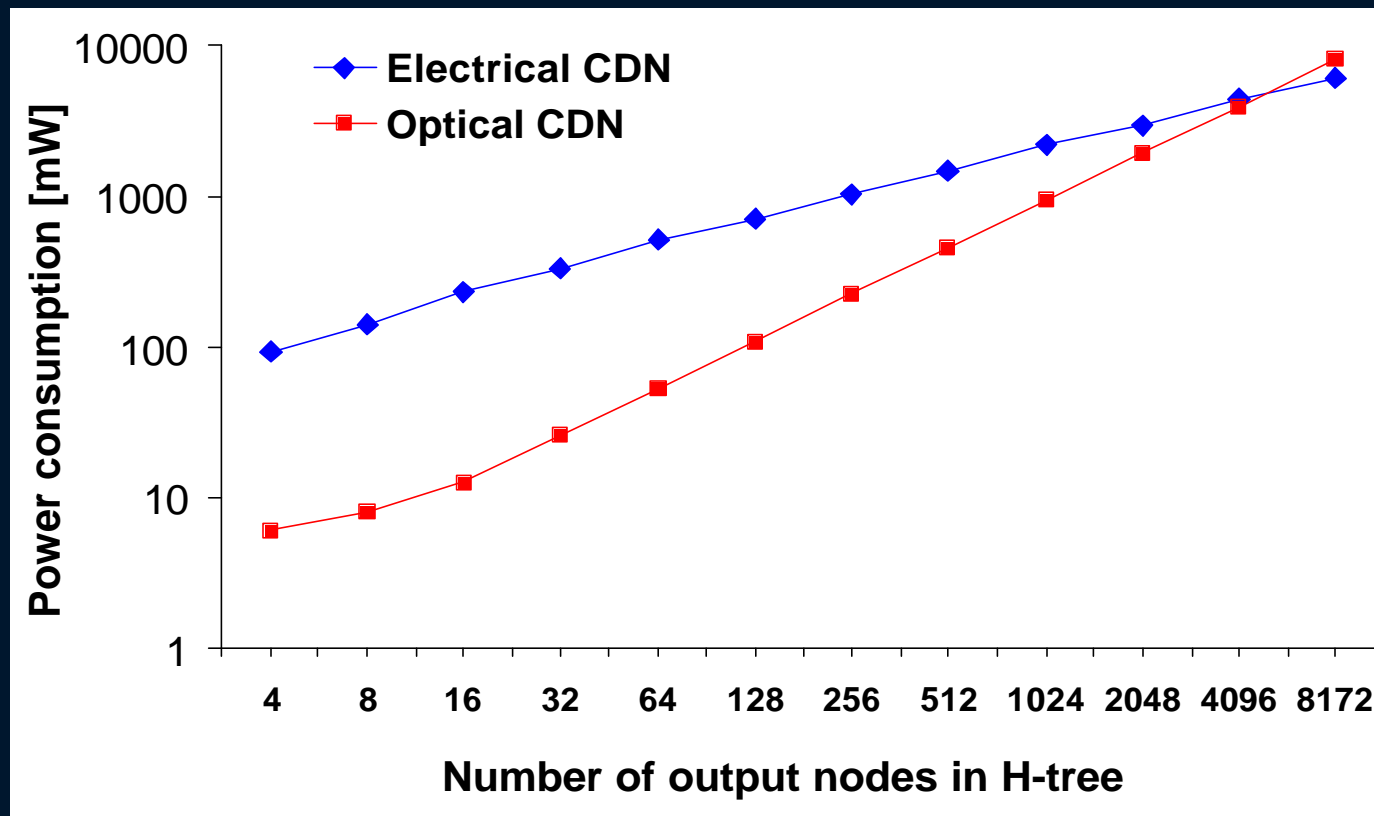
# Electrical-optical comparison

- comparing optical clock distribution power dissipation for varying operating frequency
- @70nm node, 20mm chip width, 256 drop points



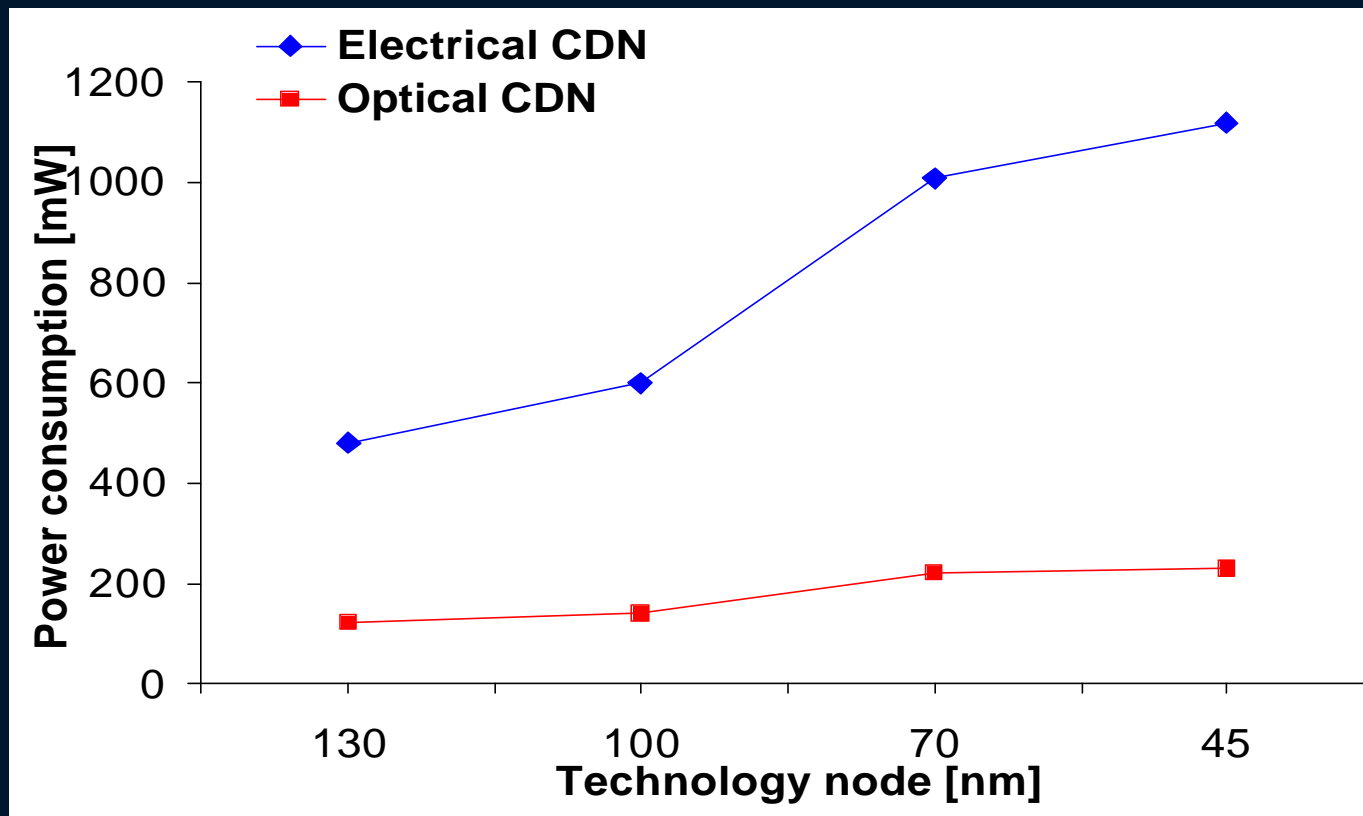
# Electrical-optical comparison

- comparing optical clock distribution power dissipation for varying number of drop points
- @70nm node, 5.6GHz, 20mm chip width



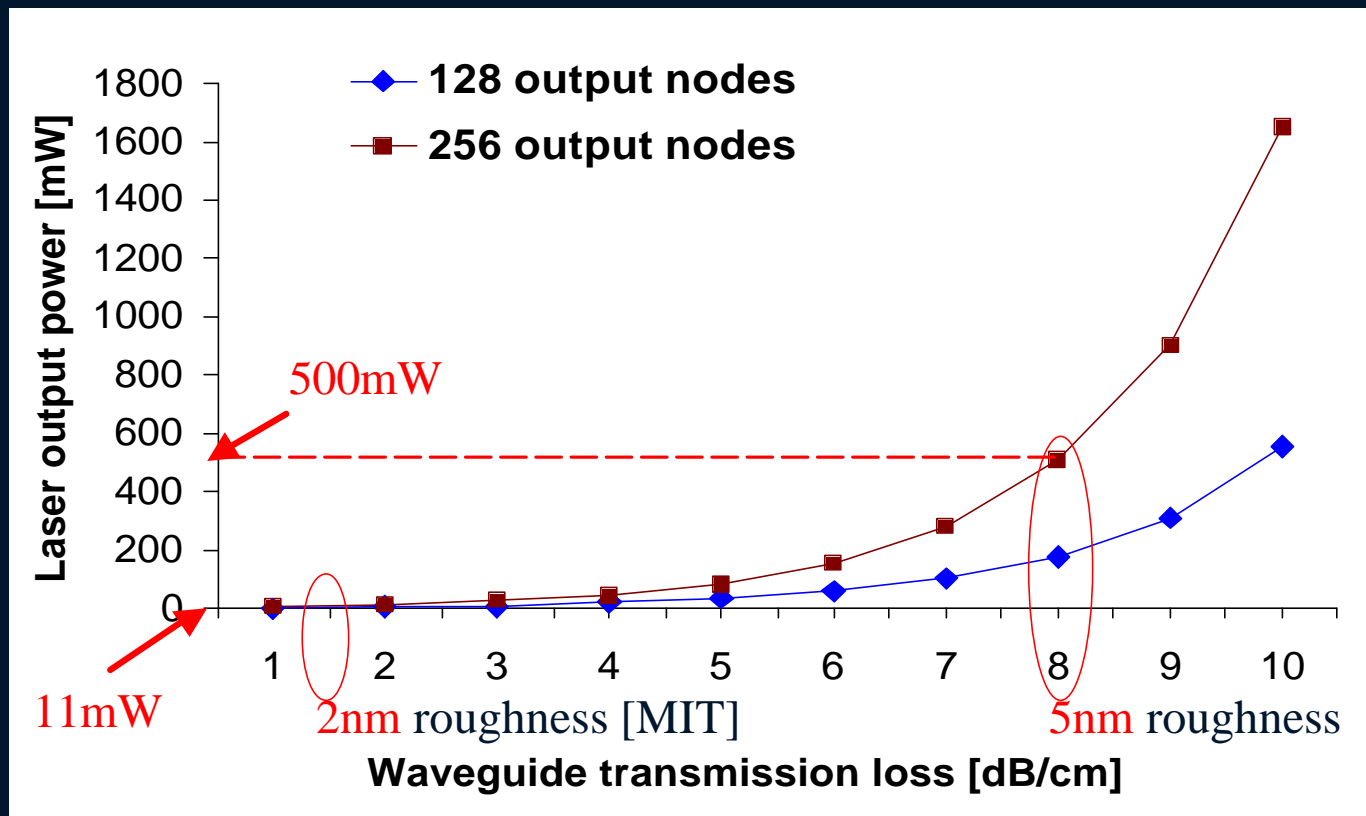
# Electrical-optical comparison

- comparing optical clock distribution power dissipation for varying technology node
- 20mm chip width, 256 drop points



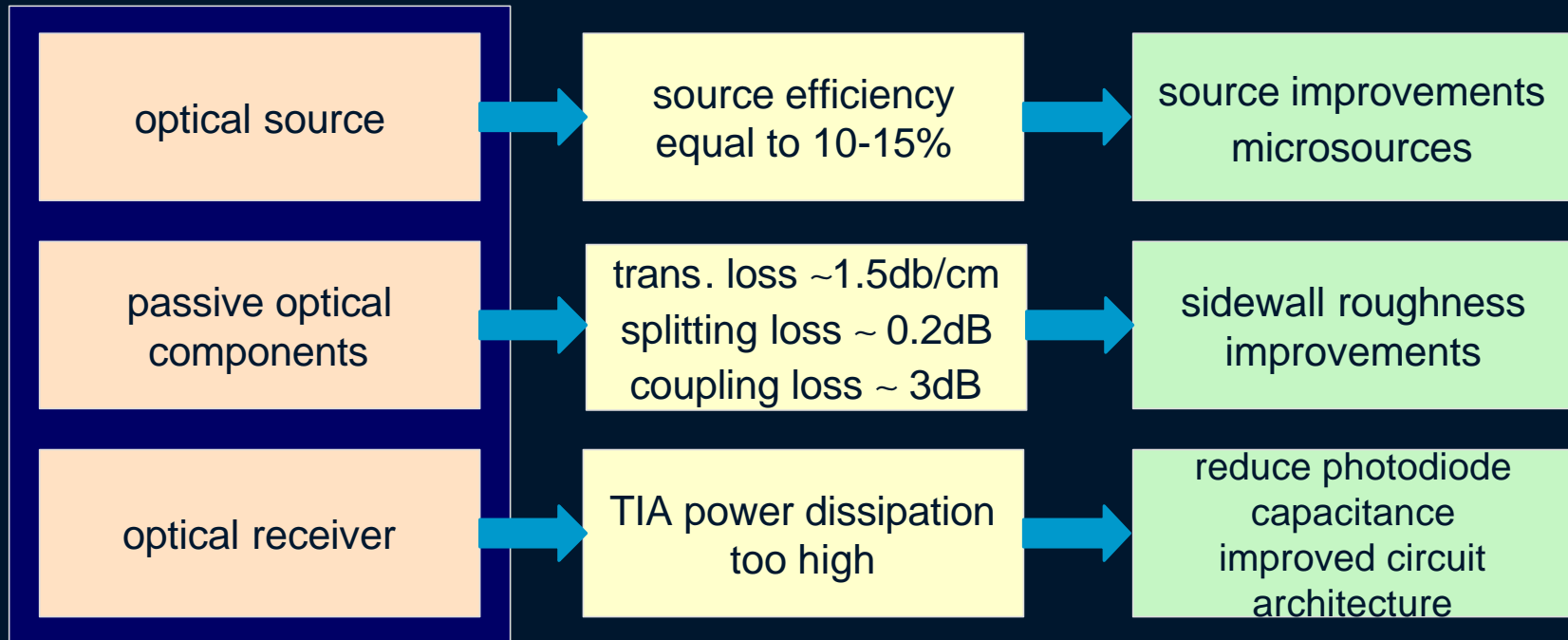
# Electrical-optical comparison

- comparing optical clock distribution power dissipation for varying sidewall roughness
- @70nm node, 5.6GHz, 20mm chip width, BER=10<sup>-15</sup>



# Clock distribution conclusions

- optical clock distribution gives a five-fold improvement in power dissipation at 5GHz
- this factor will increase as optical technology improves and operating frequencies rise
- where is work needed?



- more details at DATE Wednesday session 5G 12:00

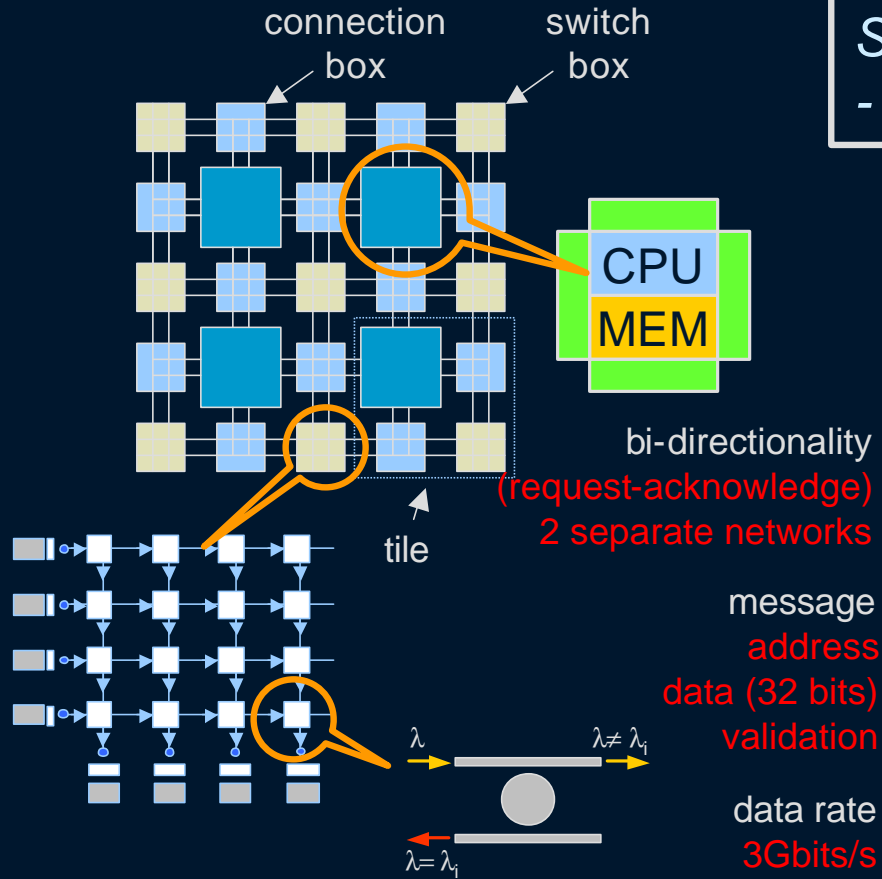
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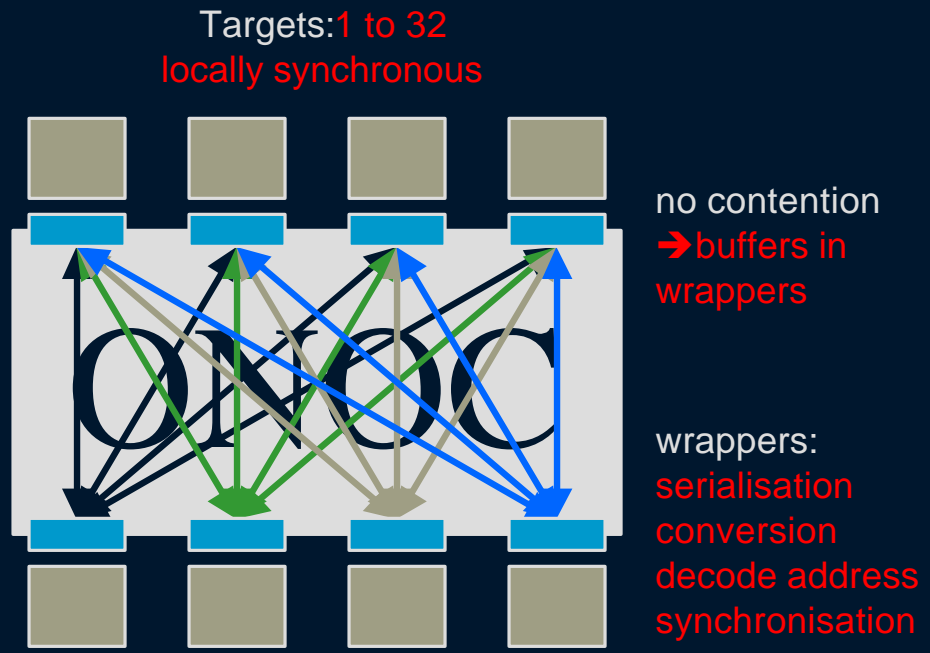
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# Reconfigurable optical NoCs (N-N)

*SoC architectures*  
- distributed heterogeneous resources



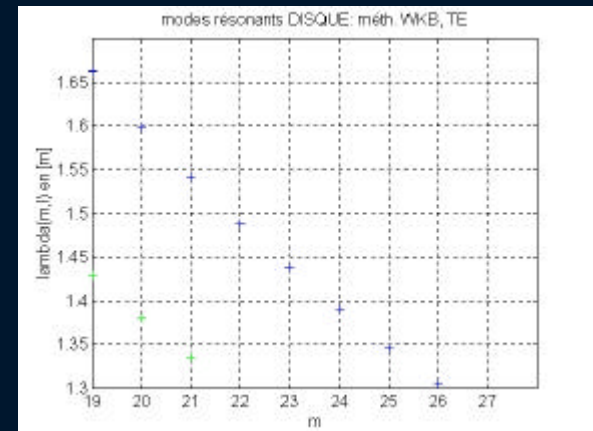
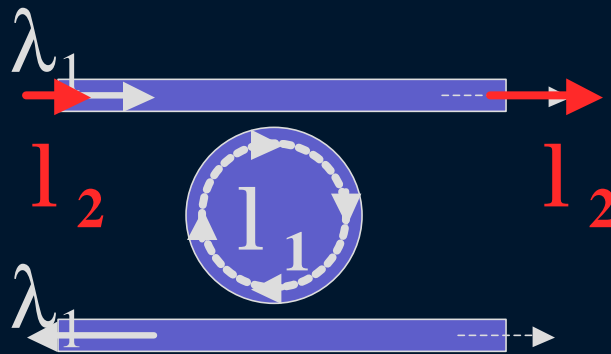
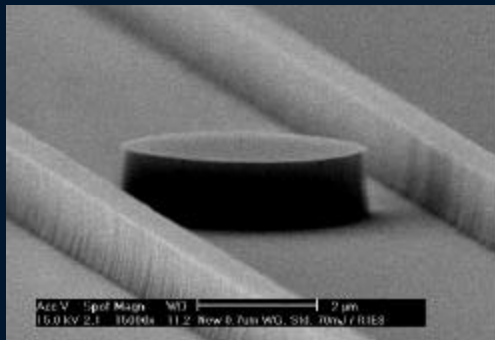
*MMP architectures*  
- distributed memory, and/or  
- memory accessible through CPU



*Comparison with SPIN (LIP6)*

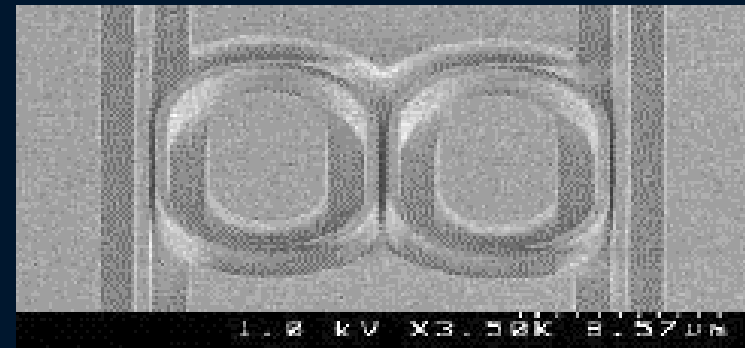
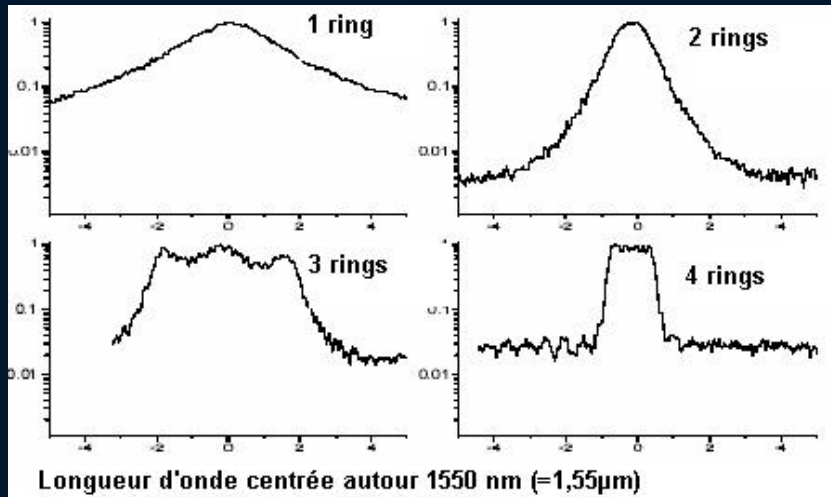
# Microring resonator

- depending on the disc material parameters and dimensions, several resonant wavelengths exist
- lightwave will couple into the disc (and then out via the other waveguide) if its wavelength is equal to one of the microring's resonant wavelengths
- otherwise there is no coupling and the lightwave propagates normally
- selectivity critical factor in number of channels
- estimation of sensitivity of  $\lambda_k$  to mismatch ...



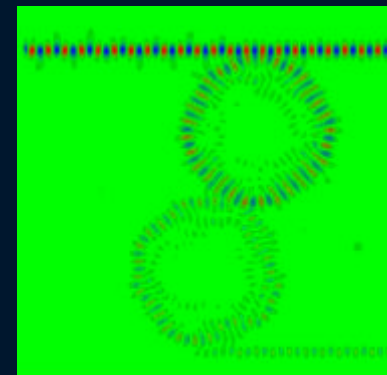
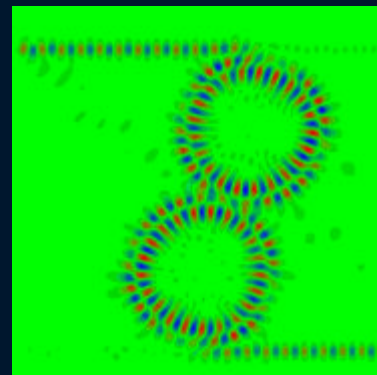
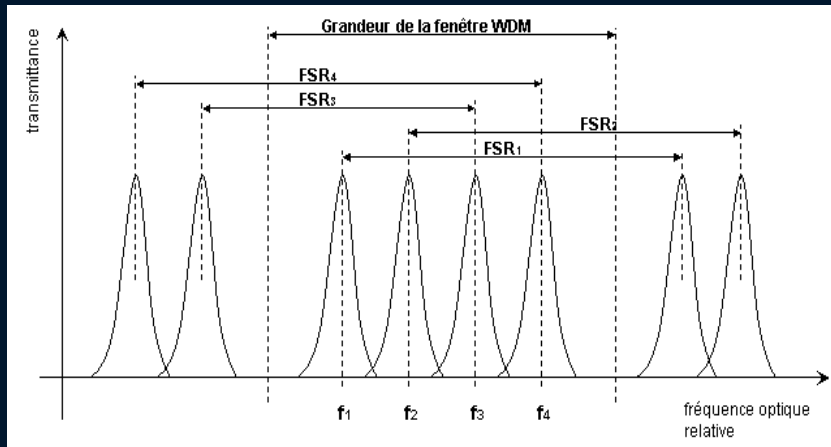
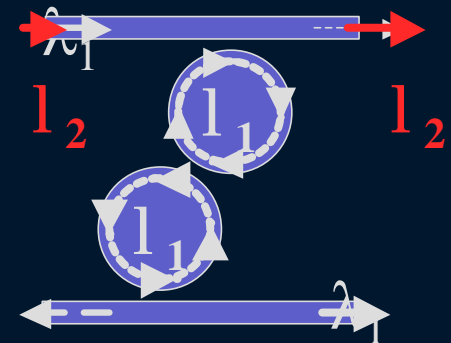


# Microring selectivity and FSR



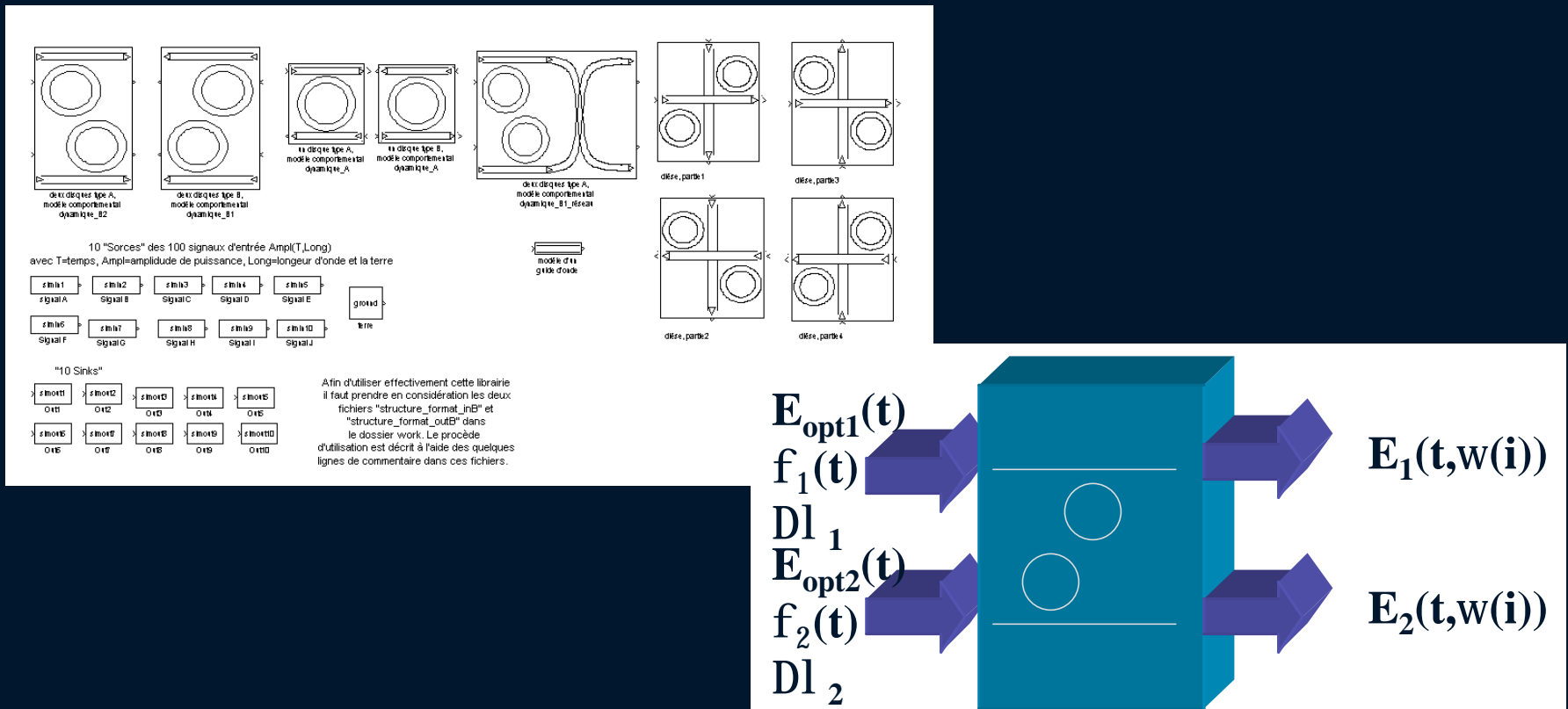
$$P(w) = \left( \frac{4/t_0^2}{4/t_0^2 + (w - w_0)^2} \right)^N$$

$$\begin{cases} \frac{\partial \vec{H}}{\partial t} = -\frac{1}{m} \nabla \times \vec{E} \\ \frac{\partial \vec{E}}{\partial t} = \frac{1}{e} \nabla \times \vec{H} \\ \nabla \cdot \vec{D} = 0 \\ \nabla \cdot \vec{B} = 0 \end{cases}$$



# Models for system design

- library of building blocks (Matlab and VHDL-AMS)
  - equation capture for all elements
  - parameter extraction for model simulation
  - simulation results: power, attenuation, data rate ...



# Design environment

File Edit Tools Window Help

**Choisir des valeurs pour les paramètres du fichier "inbelWDM.m" et appuyer sur 'Mis à jour':**

---

Choisir le nombre des canaux WDM:  1  2  3  4  5  6  7  8  9  10

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Lambda1 : début de la bande de fréquence (en  $\mu\text{m}$ ):       Lambda2 : fin de la bande de fréquence (en  $\mu\text{m}$ ):

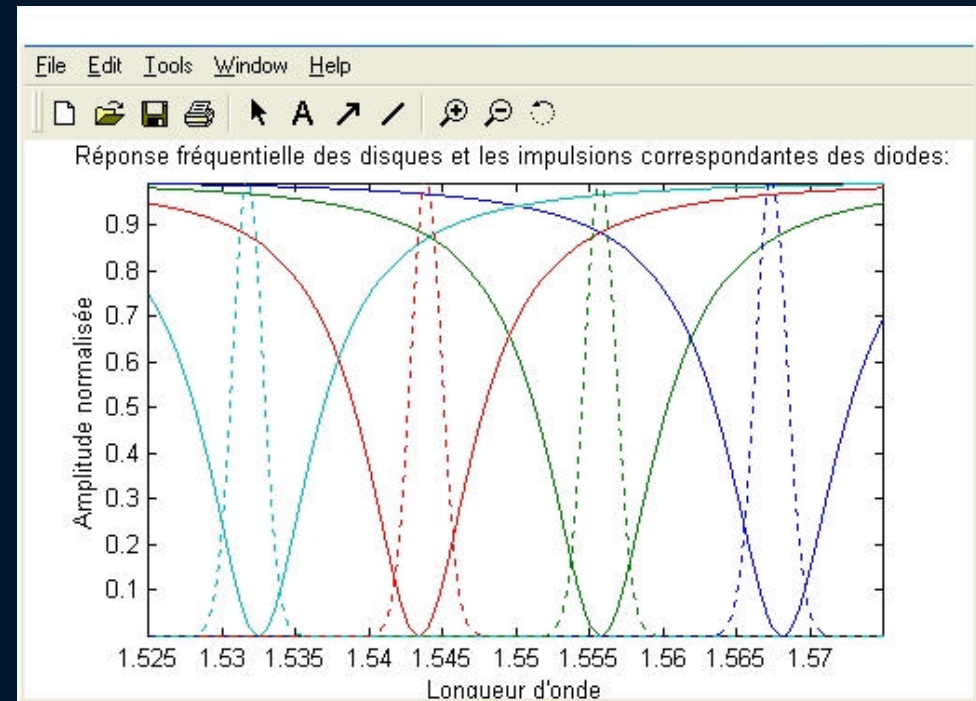
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n : indice de réfraction du matériel ( $c=c/n$ ): <input type="text" value="3.5"/>	Dist: type de distribution pour les valeurs m et q: <input checked="" type="radio"/> Dist. normale <input type="radio"/> loi uniforme
dio: détermine la grandeur de l'impulsion, $H=1*\exp\{-\text{dio}*(w-w_0)^2\}$ , la grandeur $\sim 1/\text{dio}$ : <input type="text" value="3e-012"/>	m : dét. l'éloignement max. de la longueur d'onde de résonance du disque, +/-m en nm: <input type="text" value="1.1"/>
Utiliser dellam ou dio <input type="checkbox"/>	q : dét. l'éloignement max. des milieux des canaux WDM (bande de fréq. de la diode) +/-q en nm: <input type="text" value="0.7"/>
dellam: grandeur de l'impulsion au milieu en $\mu\text{m}$ : <input type="text" value="0.01"/>	pire : Utilisation du cas le plus pire pour q et m: <input type="checkbox"/>
to: "time of decay" du microrésonateur en s ( $1\text{ps}=1*10^{-12}\text{s}$ ): <input type="text" value="2e-012"/>	
Le nombre des microdisques du microrésonateur: <input checked="" type="radio"/> 1 <input type="radio"/> 2 <input type="radio"/> 3	

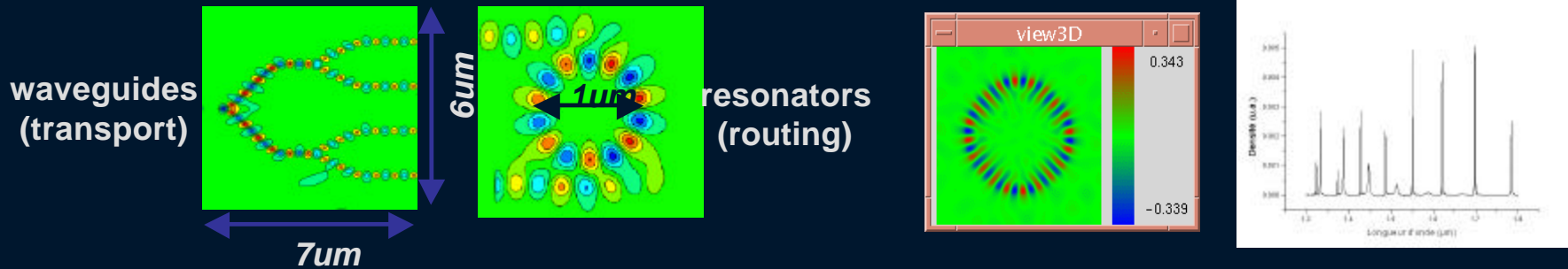
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Mis à jour    FIN    Type de représentation des résultats du filtrage:  restes du filtrage   
  canaux filtrés

Tenir compte de la diaphonie:



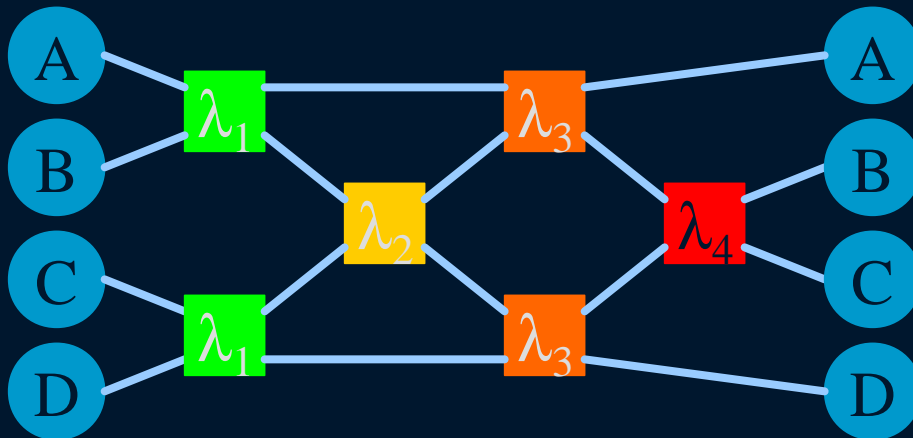
# Photonic device simulation tools



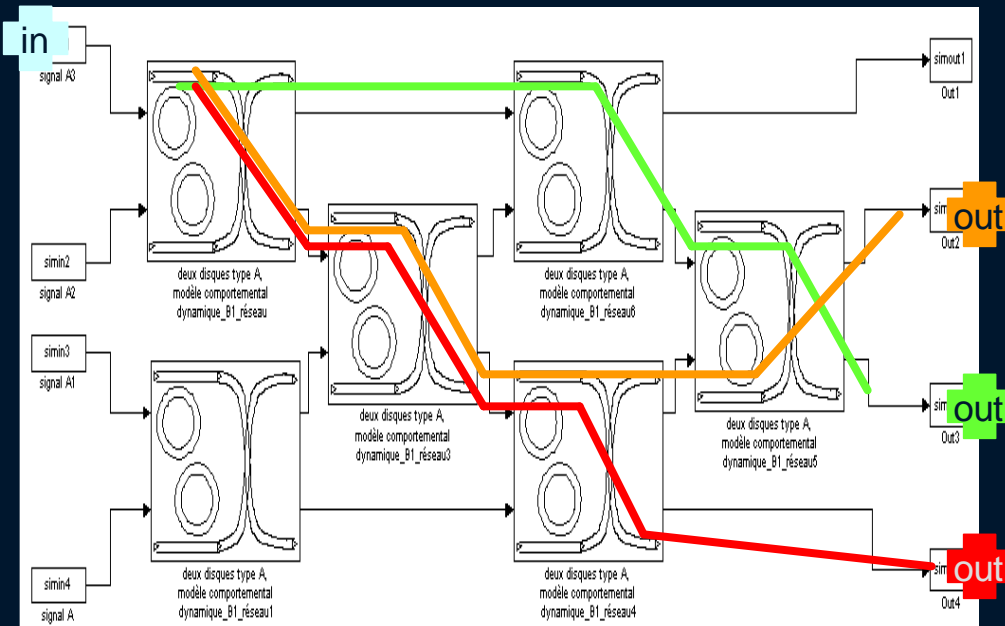
- 2D-3D FDTD (finite difference time domain) method
- simulation engine integrated into standard EDA environment (Cadence)
- parallel execution and memory bus usage optimization



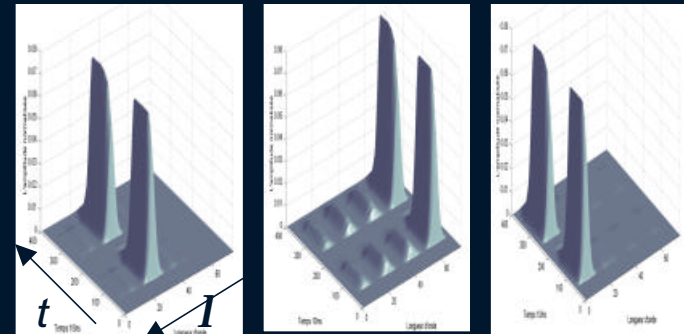
# Modelling and simulation of an optical crossbar



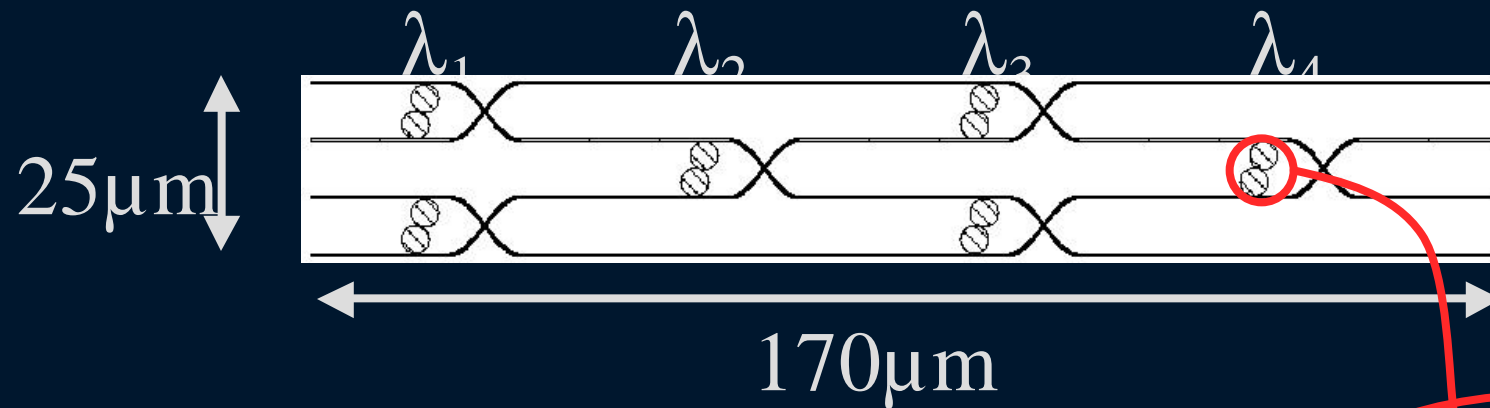
		receiver			
		A	B	C	D
emitter	A	$\lambda_2$	$\lambda_3$	$\lambda_1$	$\lambda_4$
	B	$\lambda_3$	$\lambda_4$	$\lambda_2$	$\lambda_1$
	C	$\lambda_1$	$\lambda_2$	$\lambda_4$	$\lambda_3$
	D	$\lambda_4$	$\lambda_1$	$\lambda_3$	$\lambda_2$



Injection in port #1

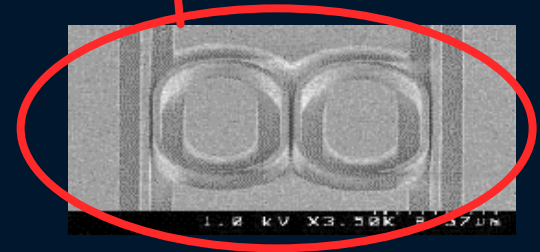


# 4x4 optical cross-bar



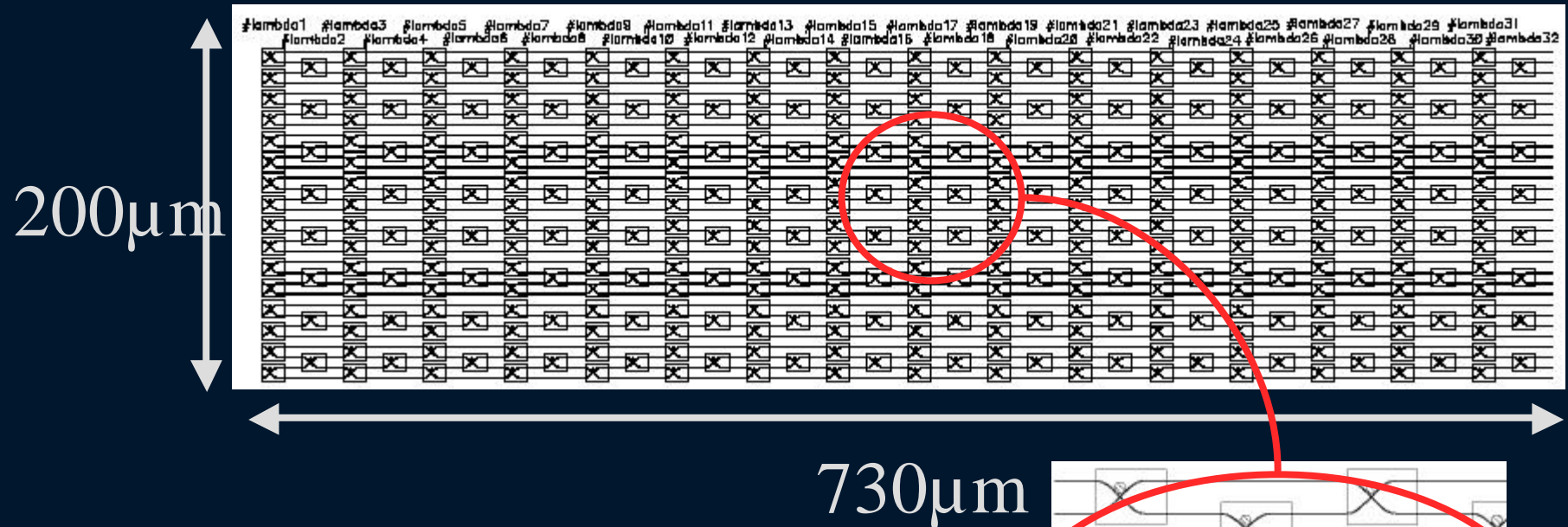
Total area for passive network: 0.00425 mm<sup>2</sup>

↗ + Connections to SoC IP blocks





# 32x32 optical cross-bar



Total area for passive network:  
 $0.146 \text{ mm}^2$

# Conclusion

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- optical links are moving into the chip
- first quantitative comparisons show an advantage for optical clock distribution over electrical schemes
- but is it enough?
- do we really need global clock distribution?
- optical network on chip promising:
  - scalable passive structure developed, test under way
  - low real estate, high throughput, should be full-duplex
- high-level models necessary for design (SystemC)
- watch this space for quantitative comparison
- more details at DATE:
  - Wednesday session 4E 10:30 and session IP3 11:00
  - Friday W2 Parallel optical interconnects inside electronic systems